



PATENT Attorney Docket No. 2887.0261

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re A	Application of:)
томо	DHIRO SAITO))
Applic	ation No.: 10/730,903) Group Art Unit: 2811
Filed:	December 10, 2003) Examiner: Unknown
For:	SEMICONDUCTOR DEVICE AND METHOD OF MANUFACTURING THE SAME)))

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), applicant brings to the attention of the Examiner the documents listed on the attached PTO 1449. This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits for the above-referenced application.

Copies of the listed documents are attached.

Applicant respectfully requests that the Examiner consider the listed documents and indicate that they were considered by making appropriate notations on the attached form.

An English-language abstract is also provided for the non-English-language document.

The following is a concise statement of relevance of the non-English language document:

Japanese Patent Publication No. 2000-294557 discloses prevention of overpolishing by using dummy patterns. The relevance of this document is also discussed at page 2 of the present application.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicant determines that the cited documents do not constitute "prior art" under United States law, applicant reserves the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

Applicant further reserves the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER, L.L.P.

Dated:

By:__<u>//(</u>

Richard V. Burgujiar

Reg. No. 31,7

INFORMATION DISCLOSURE CITATION

	INFORMAT	ION DISCLOSURE	CHAHON	OIPE
Atty. Docket No.	2887.0261	Appln. No.	10/730,903	70
Applicant	Saito			R JUL 1 4 2004 H
Filing Date	December 10, 2003	Group:	2811	EL S
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	U.S. PATENT DOCUMENTS					
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
	6,054,355	4/25/00	Inumiya et al.			
3343331						

FOREIGN PATENT DOCUMENTS						
	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
	2000-294557	10/20/00	Japan			Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)				
Saito et al., "Plasma-Damage-Free Gate Process Using Chemical Mechanical Polishing for 0.1 µm MOSFETs," Jpn. J. Appl. Phys. (April 1999), 38:2227-31				

Examiner		Date Considered	
*Examiner:		erence considered, whether or not citation is in conformance with MPEP 609; draw line ation if not in conformance and not considered. Include copy of this form with next ation to applicant.	
Form PTO 144	9 Patent and	Trademark Office - U.S. Department of Commerce	